

MOSIS WAFER ACCEPTANCE TESTS

RUN: T6BF TECHNOLOGY: SCN15 RUN TYPE: SKD FEATURE SIZE: 1.6 microns VENDOR: AMIS

INTRODUCTION: This report contains the lot average results obtained by MOSIS from measurements of MOSIS test structures on each wafer of this fabrication lot. SPICE parameters obtained from similar measurements on a selected wafer are also attached.

COMMENTS: SCNA16_AMIS

TRANSISTOR PARAMETERS	W/L	N-CHANNEL	P-CHANNEL	UNITS
MINIMUM	4.0/1.6			
Vth		0.57	-0.97	volts
SHORT	20.0/1.6			
Idss		183	-72	uA/um
Vth		0.55	-0.93	volts
Vpt		10.0	-10.0	volts
WIDE	20.0/1.6			
Ids0		< 2.5	< 2.5	pA/um
LARGE	50/50			
Vth		0.58	-0.88	volts
Vjbkd		16.6	-14.5	volts
Ijlk		<50.0	<50.0	pA
Gamma		0.62	0.47	V^0.5
K' (Uo*Cox/2)		35.7	-12.0	uA/V^2
Low-field Mobility		632.73	212.68	cm^2/V*s

Each wafer fabrication run has its own code; this run is designated "T6BF"

FEATURE SIZE is the minimum gate length; 1.6μm for this process

TECHNOLOGY and RUN TYPE are more specific; these codes indicate added features in the process (for example, linear capacitors and BJTs)

Vth is the threshold voltage; MINIMUM refers to the smallest geometry devices allowed by the process design rules. For logic applications, often only minimum size devices are used.

Idss is the current per unit width with maximum voltage (in the case of this process, 5V) applied for VGS. Expressing current this way allows the designer to rapidly determine required device size for a given current. For example, if 2mA of drive current is required for a P-channel MOSFET when the gate is fully turned on, the width should be $2\text{mA} / (86\mu\text{A}/\mu\text{m}) = 23.3\mu\text{m}$. Note also that the threshold voltage Vth for the SHORT device is different than the MINIMUM case -- a second-order effect that SPICE needs to keep track of. Vpt is the punch-through voltage, beyond which the device will be damaged.

This is the leakage current per unit width when VGS=0. An important parameter for analog switch design, especially in sample-and-hold circuits when the hold capacitor can be partially discharged by the leakage current of a MOSFET which should be "off".

Again, note that the threshold voltage is affected by device geometry. Vjbkd is the breakdown voltage of the active-substrate pn junction; Ijlk is the reverse bias leakage current of the junction. Gamma is the body-effect parameter, which expresses how the threshold voltage is affected by the source-substrate reverse bias voltage.

K' is the transconductance parameter used in some expressions of the square law

$$I_D = \underbrace{\frac{\mu C_{OX}}{2}}_{K'} \frac{W}{L} (V_{GS} - V_{TH})^2$$

Low-field mobility is the value of μ for E fields below the velocity saturation limited region.

COMMENTS: Poly bias varies with design technology. To account for mask bias use the appropriate value for the parameter XL in your SPICE model card.

Design Technology	XL (um)
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SCN (lambda=0.8)	0.00

"Poly bias" allows the software which writes the mask specification file to make the mask dimension larger or smaller than what is drawn in the layout software. This can account for the over- or under-etching of the polysilicon. Here "lambda" refers to the unit spatial dimension of the layout software used to design the masks (not the channel length modulation λ). See Razavi ch. 17 and Johns & Martin sec. 2.3 for more information.

POLY2 TRANSISTORS	W/L	N-CHANNEL	P-CHANNEL	UNITS
MINIMUM Vth	4.8/3.2	0.86	-1.14	volts
SHORT Vth	9.6/3.2	0.86	-1.09	volts
LARGE Vth	28.8/28.	0.87	-1.08	volts
K' (Uo*Cox/2)		21.5	-6.8	uA/V^2

In this technology, transistors can also be fabricated using a second polysilicon layer for the gate. The transistor parameters are different (and not quite as good) since the resulting MOSFETs have a thicker gate oxide.

FOX TRANSISTORS	GATE	N+ACTIVE	P+ACTIVE	UNITS
Vth	Poly	>15.0	<-15.0	volts

This is for a MOSFET which uses the field oxide as the gate oxide. We don't want this to function as a MOSFET (if it did, unrelated active areas could be shorted together). In this case, the field implant worked, because the threshold voltage is ~15V. Since this process is intended for 5V systems, the FOX transistor will never be on.

BIPOLAR PARAMETERS		NPN	UNITS
2X1	2X1		
Beta		129	
V_early		43.7	volts
Vce,sat		---	volts
2X2	2X2		
Beta		131	
V_early		43.7	volts
Vce,sat		---	volts
2X4	2X4		
Beta		131	
V_early		43.4	volts
Vce,sat		---	volts
2X8	2X8		
Beta		130	
V_early		43.2	volts
Vce,sat		---	volts
BVceo		18.9	volts
BVcbo		30.2	volts
BVebo		8.0	volts

This process technology includes layers that allow fabrication of NPN bipolar transistors. It turns out that these BJTs have reasonably good DC performance, but not very good high frequency performance. Usually these devices would be used in a circuit such as the bandgap voltage reference which makes use of the exponential voltage-current behavior of the BJT in developing a temperature-stable DC reference voltage.

PROCESS PARAMETERS	N+	P+	POLY	POLY2	PBASE	M1	M2	UNITS
Sheet Resistance	52.2	75.6	25.0	22.3	2257.5	0.05	0.03	ohms/sq
Contact Resistance	54.5	41.1	25.4	17.0			0.05	ohms
Gate Oxide Thickness	306							angstrom

PROCESS PARAMETERS	N_W	UNITS
Sheet Resistance	1714	ohms/sq
Contact Resistance		ohms

Contact resistance: This is the resistance of one contact between METAL1 and the layer indicated. For example, one contact between the heavily doped N-type source or drain region of a MOSFET (N+) and the first layer of metal (M1) has a resistance of 54.5Ω - not negligible! When it is necessary to lower resistance, many contacts are made in parallel to give a lower total resistance.

Gate Oxide Thickness: This is the oxide thickness t_{ox} used to determine the gate capacitance per unit area. Check by comparing to the gate oxide capacitance per unit area:

$$\frac{\epsilon_{ox}}{t_{ox}} = \frac{K_{ox}\epsilon_0}{t_{ox}} = \frac{3.9(8.85E-12 F/m)}{306E-10 m} = 1.13E-3 F/m^2$$

Which agrees pretty well with the $1128aF/\mu m^2$ for POLY-to-N+ shown below

CAPACITANCE PARAMETERS	N+	P+	POLY	POLY2	M1	M2	N_W	UNITS
Area (substrate)	291	302	36	37	21	13	129	aF/ μm^2
Area (N+active)			1128	730	50	26		aF/ μm^2
Area (P+active)			1110	723				aF/ μm^2
Area (poly)				592	46	23		aF/ μm^2
Area (poly2)					46	23		aF/ μm^2
Area (metall)						38		aF/ μm^2
Fringe (substrate)	79	160			31	27		aF/ μm
Fringe (poly)					58	44		aF/ μm
Fringe (metall)						55		aF/ μm
Overlap (N+active)			173					aF/ μm
Overlap (P+active)			231					aF/ μm

Sheet resistance: These are the numbers to use when determining the physical dimensions of a resistor to achieve a certain value of resistance. The layers are:

- N+** Heavily doped region of N-type diffusion used for source, drain of N-channel MOSFETs
- P+** Heavily doped region of P-type diffusion used for source, drain of P-channel MOSFETs
- POLY** Polysilicon metal used for gates of MOSFETs
- POLY2** A second layer of polysilicon which can also be used for MOSFET gates (Also, POLY and POLY2 can be used with thin oxide between to make a linear capacitor (See capacitance parameters below)
- PBASE** A moderately doped region of P-type diffusion used as the base for NPN bipolar transistors
- M1** First layer of aluminum metallization; much lower sheet resistance than polysilicon or diffusion
- M2** Second layer of metallization; lowest sheet resistance since thickness of M2 is greater than thickness of M1
- N_W** Lightly doped region of N-type diffusion used as a well (sort of a "local substrate") used for P-channel MOSFETs

These are parallel-plate capacitance (per unit area) between the layers indicated. For example, a capacitor using M1 and M2 as the plates will have a capacitance of $38aF/\mu m^2$ (atto is $1E-18$) per micron squared. A capacitor $100\mu m \times 100\mu m$ has an area of $1E+4\mu m^2$, so the capacitance would be $380E-15 F$, or $0.38pF$.

Fringe and overlap capacitances are edge effects, and therefore are given per unit length. The $100\mu m \times 100\mu m$ capacitor mentioned in the example above would have a perimeter of $400\mu m$. The fringe capacitance from M1 to M2 is $55aF/\mu m$. Thus the capacitance due to the fringing field would be $(400\mu m)(55aF/\mu m) = 22E-15 F = 22fF$. Total for the $100\mu m \times 100\mu m$ capacitor will be the sum of contributions from parallel plate + fringing: $0.38pF + 22fF = 0.402pF$.

CIRCUIT PARAMETERS

	K		UNITS
Inverters			
V _{inv}	1.0	1.80	volts
V _{inv}	1.5	2.11	volts
V _{ol} (100 uA)	2.0	0.44	volts
V _{oh} (100 uA)	2.0	4.33	volts
V _{inv}	2.0	2.31	volts
Gain	2.0	-15.06	
Ring Oscillator Freq.			
DIV64 (31-stg,5.0V)		37.70	MHz
Ring Oscillator Power			
DIV64 (31-stg,5.0V)		1.60	uW/MHz/gate

This data describes performance of CMOS logic inverters. "K" is the size ratio between the P-channel and N-channel MOSFETs in the CMOS inverter. For example, for the case K=1.5, the PMOS device in the inverter has a width 1.5X the NMOS width.

V_{inv} is the logic threshold of the inverter.

V_{ol} and V_{oh} are the output voltages the inverter output can maintain while sourcing (V_{oh}) or sinking (V_{ol}) the indicated current of 100μA.

Gain is the slope of the V_{out} vs. V_{in} transfer characteristic of the inverter at its switching threshold. Although it might seem irrelevant to worry about an "analog" concept like gain in a digital system, it is actually very important that the gain magnitude be greater than unity: if the gain is less than one, logic swings become smaller and smaller as a logic signal propagates through a sequence of gates, until the logic swing is too small to switch a gate at all.

A ring oscillator is made up of a chain of inverters with a net signal inversion from input to output (enforced in this case by using an odd number of inverters). When the output of the chain is tied back to the input, this completes a ring, and a signal edge will propagate around the ring, forming an oscillator. The oscillation frequency is

$$f_{osc} = \frac{1}{2 \cdot N \cdot t_{PD}}$$

where N is the number of stages in the ring and t_{PD} is the propagation delay of the inverter. Thus measuring the ring oscillator frequency is an easy way to determine the propagation delay of the logic inverter; in this case with an oscillator frequency of f_{osc} = 37.7 MHz it is

$$t_{PD} = \frac{1}{2 \cdot N \cdot f_{osc}} = \frac{1}{2 \cdot 31 \cdot (37.7E + 6 \text{ Hz})} = 428 \text{ ps}$$

The ring oscillator power measurement can be used to estimate the power consumed by a digital circuit given the number of gates and the switching frequency.

T6BF SPICE LEVEL3 parameters are available for classroom instructional purposes but not for actual IC design work.

```
* DATE: Jan 12/07
* LOT: T6BF                      WAF: 6102
* Temperature_parameters=Default
.MODEL CMOSN NMOS (
+ TOX      = 3.06E-8           NSUB    = 9.34116E15      LEVEL  = 3
+ PHI      = 0.9554462        VTO     = 0.6111337      GAMMA  = 0.7671649
+ UO       = 541.3782915      ETA     = 6.06068E-4      DELTA  = 0.7532645
+ KP       = 7.399509E-5      VMAX   = 2.102169E5     THETA  = 0.070589
+ RSH      = 23.7230709      NFS     = 6.009445E11    KAPPA  = 0.5
+ XJ       = 3E-7            LD       = 8.616976E-15    TPG    = 1
+ CGDO     = 1.73E-10        CGSO    = 1.73E-10      WD     = 6.516763E-7
+ CJ       = 2.872743E-4     PB      = 0.838875    CGBO   = 1E-10
+ CJSW     = 1.238328E-10    MJSW    = 0.05        MJ     = 0.5
*
.MODEL CMOSP PMOS (
+ TOX      = 3.06E-8           NSUB    = 1E17      LEVEL  = 3
+ PHI      = 0.7              VTO     = -0.889286   GAMMA  = 0.4950231
+ UO       = 100              ETA     = 9.990442E-5   DELTA  = 0.2719659
+ KP       = 2.524773E-5      VMAX   = 1.930155E5   THETA  = 0.1262713
+ RSH      = 0.2004376      NFS     = 5.850358E11    KAPPA  = 90
+ XJ       = 2E-7            LD       = 1.001708E-14    TPG    = -1
+ CGDO     = 2.31E-10        CGSO    = 2.31E-10      WD     = 9.821909E-7
+ CJ       = 2.993018E-4     PB      = 0.8        CGBO   = 1E-10
+ CJSW     = 1.609243E-10    MJSW    = 0.1174914   MJ     = 0.4481429
*
)
```

These are the SPICE parameters that would be used for simulating the MOSFET using the Level 3 model. Note that you are cautioned not to use these parameters for actual IC design work! The more accurate, but more complicated, Level 49 BSIM3 model parameters are given on the next two pages.

To simulate using the parameters you extract in the studio labs for the MC14007 MOSFET, you will use a (much simpler) set of model parameters based on the parameters extracted from your lab measurements.

T6BF SPICE BSIM3 VERSION 3.1 PARAMETERS

SPICE 3f5 Level 8, Star-HSPICE Level 49, UTMOST Level 8

* DATE: Jan 12/07

* LOT: T6BF WAF: 6102

* Temperature_parameters=Default

```
.MODEL CMOSN NMOS (
+VERSION = 3.1          TNOM    = 27          LEVEL   = 49
+XJ      = 3E-7         NCH     = 7.5E16       TOX      = 3.06E-8
+K1      = 0.9040053    K2      = -0.0667247    VTH0     = 0.5467907
+K3B     = -2.4863898   W0      = 1.726569E-6    K3       = 3.2074393
+DVT0W   = 0           DVT1W   = 0           NLX     = 2.003139E-8
+DVT0    = 0.5616596   DVT1    = 0.5961287    DVT2W    = 0
+U0      = 659.1539164  UA      = 1.571393E-9    DVT2     = -0.5
+UC      = 1.327941E-11 VSAT   = 9.85294E4    UB       = 6.331182E-19
+AGS     = 0.1306233    B0     = 2.470264E-6    A0       = 0.5995609
+KETA    = -0.0107507   A1     = 0           B1       = 5E-6
+RDSW    = 3E3         PRWG    = -0.0293948    A2       = 1
+WR      = 1           WINT    = 6.909849E-7    PRWB     = -0.0296004
+XL      = 0           XW      = 0           LINT     = 2.918303E-7
+DWB     = 2.842396E-8  VOFF   = -0.0700562    DWG      = -1.088946E-8
+CIT      = 0          CDSC    = 8.279564E-8    NFACTOR  = 0.4708962
+CDSCB   = 3.869072E-5  ETA0   = 0.0110351    CDSCD    = 1.482736E-6
+DSUB    = 0.2442264   PCLM   = 0.2186109    ETAB     = 0.0262778
+PDIBLC2 = 3.644817E-3 PDIBLCB = -0.1        PDIBLC1  = 0.0110461
+PSCBE1  = 2.153596E9  PSCBE2 = 5.005E-10    DROUT    = 0.0795384
+DELTA   = 0.01        RSH     = 52.2        PVAG     = 0.2222499
+PRT      = 0          UTE     = -1.5        MOBMOD   = 1
+KT1L    = 0          KT2     = 0.022        KT1      = -0.11
+UB1     = -7.61E-18   UC1     = -5.6E-11    UA1      = 4.31E-9
+WL      = 0          WLN     = 1          AT       = 3.3E4
+WWN     = 1          WWL     = 0          WW       = 0
+LLN     = 1          LW      = 0          LL       = 0
+LWL     = 0          CAPMOD  = 2          LWN      = 1
+CGDO    = 1.73E-10    CGSO    = 1.73E-10    XPART    = 0.5
+CJ      = 2.767682E-4  PB      = 0.99        CGBO     = 2E-9
+CJSW    = 1.417238E-10 PBSW    = 0.9889456    MJ       = 0.5559833
+CJSWG   = 6.4E-11     PBSWG   = 0.9889456    MJSW     = 0.1
+CF      = 0           )      MJSWG    = 0.1
*
```

.MODEL CMOS PMOS (		LEVEL = 49
+VERSION = 3.1	TNOM = 27	TOX = 3.06E-8
+XJ = 3E-7	NCH = 2.4E16	VTH0 = -0.8476404
+K1 = 0.4513608	K2 = 2.379699E-5	K3 = 13.3278347
+K3B = -2.2238332	W0 = 9.577236E-7	NLX = 4.909017E-7
+DVT0W = 0	DVT1W = 0	DVT2W = 0
+DVT0 = 0.7546343	DVT1 = 0.4613224	DVT2 = -0.179467
+U0 = 236.8923827	UA = 3.833306E-9	UB = 1.487688E-21
+UC = -1.08562E-10	VSAT = 1.842738E5	A0 = 0.3536635
+AGS = 0.2659996	B0 = 1.980132E-6	B1 = 5E-6
+KETA = 0.0303949	A1 = 0	A2 = 0.364
+RDSW = 3E3	PRWG = 0.0725853	PRWB = -0.1860065
+WR = 1	WINT = 7.565065E-7	LINT = 1.422522E-7
+XL = 0	XW = 0	DWG = -2.13917E-8
+DWB = 3.857544E-8	VOFF = -0.0877184	NFACTOR = 0.2508342
+CIT = 0	CDSC = 2.924806E-5	CDSCD = 1.497572E-4
+CDSCB = 1.091488E-4	ETA0 = 0.20103	ETAB = -0.0129682
+DSUB = 0.2873	PCLM = 6.403032E-10	PDIBLC1 = 7.477411E-4
+PDIBLC2 = 3.271335E-3	PDIBLCB = -1E-3	DROUT = 1E-3
+PSCBE1 = 3.515038E9	PSCBE2 = 5.273648E-10	PVAG = 14.985
+DELTA = 0.01	RSH = 75.6	MOBMOD = 1
+PRT = 0	UTE = -1.5	KT1 = -0.11
+KT1L = 0	KT2 = 0.022	UA1 = 4.31E-9
+UB1 = -7.61E-18	UC1 = -5.6E-11	AT = 3.3E4
+WL = 0	WLN = 1	WW = 0
+WWN = 1	WWL = 0	LL = 0
+LLN = 1	LW = 0	LWN = 1
+LWL = 0	CAPMOD = 2	XPART = 0.5
+CGDO = 2.31E-10	CGSO = 2.31E-10	CGBO = 2E-9
+CJ = 2.995053E-4	PB = 0.8	MJ = 0.4487006
+CJSW = 1.586304E-10	PBSW = 0.8971831	MJSW = 0.1136092
+CJSWG = 3.9E-11	PBSWG = 0.8971831	MJSWG = 0.1136092
+CF = 0	)	
*		